

N THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: TANAKA, Yasuaki

Group Art Unit: 1756

Serial No.: 10/042,345

Examiner: NICOLE M. BARRECA

Filed: January 11, 2002

P.T.O. Confirmation No.: 6310

FOR: PROJECTION APPARATUS, METHOD OF MANUFACTURING THE APPARATUS,

METHOD OF EXPOSURE USING THE APPARATUS, AND METHOD OF MANUFACTURING CIRCUIT DEVICES BY USING THE APPARATUS

AMENDMENT TRANSMITTAL

Commissioner for Patents Washington, D.C. 20231

August 28, 2002

Sir:

Transmitted herewith is an Amendment in the above-identified application.

The fee has been calculated as shown below:

	CLAIMS AS AMENDED				可提供事業。 灌溉组		
	Claims Remaining After Amendment	Highest Number Previously Paid For		Present Extra	Small Entity	Large Entity	Additional Fee
Total Claims	85	73	=	12	X \$9	X \$18	216.00
Independent Claims	10	10		0	X \$42	X \$84	0.00
First Presentation of Multiple Dependent Claims \$140 280						0.00	
TOTAL FEES ENCLOSED:							216.00

- <u>XX</u> Enclosed please find our check in the amount of 216.00 for the additional claims fee in connection with this amendment.
- XX The Commissioner is hereby authorized to charge payment for any additional fees associated with this communication or credit any overpayment to Deposit Account No. <u>01-2340</u>. Two duplicates of this sheet are attached.

RECEIVED

SEP 0 3 2002

TC 1700



Respectfully submitted,

ARMSTRONG, WESTERMAN & HATTORI, LLP

Thomas E. Brown Attorney for Applicant Reg. No. 44,450

TEB/kal

Atty. Docket No. **991482A**Suite 1000, 1725 K Street, N.W. Washington, D.C. 20006
(202) 659-2930

23850

PATENT TRADEMARK OFFICE

Q:\FLOATERS\TEB\teb\99\991482\a\Amendment Transmittal



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2a NEAL

in re the Application of: TANAKA, Yasuaki

Group Art Unit: 1756

Serial No.: 10/042,345

Examiner: NICOLE M. BARRECA

Filed: January 11, 2002

P.T.O. Confirmation No.: 6310

For. PROJECTION APPARATUS, METHOD OF MANUFACTURING THE APPARATUS, METHOD OF EXPOSURE USING THE APPARATUS, AND METHOD OF MANUFACTURING CIRCUIT DEVICES BY USING THE APPARATUS

PRELIMINARY AMENDMENT

Commissioner for Patents Washington, D.C. 20231

Date: August 28, 2002

Sir:

This is a Preliminary Amendment for the above-captioned patent application. Please amend the above-captioned patent application as follows:

IN THE CLAIMS:

Please CANCEL claims 68 - 71.

Please AMEND claims 41 - 44, 46 - 48, 52, 55 to read as follows:

41. (Amended) An exposure method for scanning exposure of a pattern formed on a mask onto a substrate through a projection optical system by moving the mask and substrate relative to an exposing energy beam,

comprising:

00000116 10042345 SEP

01 FC:103 216.00 OP

08/30/2002 MBERHE

TC 1700